

NOVEL PHENOLIC RESINS AND PHOTORESIST COMPOSITIONS
COMPRISING SAME

ABSTRACT

The invention provides these novel resins and photoresist compositions that comprise a photoactive component and one or more resins of the invention. In one aspect, resins of the invention can be characterized by use of a prepolymer reagent that is a reaction product of a methylol phenol compound. The methylol phenol compound is suitably reacted at above room temperature and/or in the presence of acid.